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		Application Number	10/781,844
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Filing Date	February 20, 2004
		First Named Inventor	Haruhiko KOMORIYA
		Art Unit	1621
		Examiner Name	Unassigned
		Attorney Docket Number	038788.53289US
Sheet	1	of	1

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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	AA	THEODORE H. FEDYNISHYN ET AL., "Fluoroaromatic Resists for 157-nm Lithography", Journal of Photopolymer Science and Technology, 2002, pp.655-666, Vol. 15, No. 4	
	AB	RALPH R. DAMMEL ET AL., "New Resin Systems for 157 nm Lithography", Journal of Photopolymer Science and Technology, 2001, pp. 603-612, Vol. 14, No. 4	

Examiner Signature		Date Considered	9/10/04
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